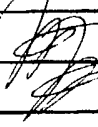
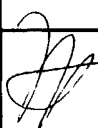


Form PTO-1449 SEP 16 2003 PATENT & TRADEMARK OFFICE		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1784		SERIAL NO. 09/930,787		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Luan Tran et al.		FILING DATE August 14, 2001		
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,736,670	4/7/1998	Carbonell et al.				
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	AC							
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	AG							
	AH							
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	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Faxon et al., "A Highly Manufacturable Trench Isolation Process for Deep Submicron DRAMs," ©1993 IEEE, 4 pages.					
	AS							
	AT							
EXAMINER				DATE CONSIDERED 12/2/03				
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